

REMARKS

This is in response to the Office Action dated October, 17, 2008. In view of the foregoing amendments and following representations, reconsideration is respectfully requested.

By the above amendment, claim 8 has been amended. Thus, claim 8 is the only claim pending in the present application.

On pages 2-3 of the Office Action, claim 8 is rejected under 35 U.S.C. 103(a) as being unpatentable over Tomita et al. (U.S. Patent No. 5,634,980) in view of Doi et al. (U.S. Patent No. 6,192,903). It is submitted that the present invention, as embodied by amended claim 8, now clearly distinguishes over the Tomita and Doi references for the following reasons.

Independent method claim 8 has been amended to recite that a reverse side of a substrate, which has been processed by a processing liquid, is cleaned with a cleaning liquid supplied from a first reverse side nozzle connected to a first cleaning liquid supply line. Claim 8 further requires that an inner wall surface of a scattering prevention cup and an upper surface of a substrate holder are cleaned with a cleaning liquid supplied from a second reverse side nozzle connected to a second cleaning liquid supply line.

In the present invention, as defined in amended claim 8, cleaning of the reverse side of the substrate with a cleaning liquid supplied from the first reverse side nozzle and cleaning of the scattering prevention cup and the upper surface of the substrate holder with a cleaning liquid supplied from the second reverse side nozzle can be carried out under optimum conditions by independently controlling the supply of a cleaning liquid through the first cleaning liquid supply line and the second cleaning liquid supply line. The claimed method provides a significant

advantage because, if a cleaning liquid were to be supplied to both the first reverse side nozzle (which necessitates two-stage flow control) and the second reverse side nozzle from one cleaning liquid supply line, adjustment of the flow rate balance becomes complex and difficult when different flow rates are supplied to the first reverse nozzle and the second reverse nozzle.

Tomita discloses a substrate washing device comprising a cleaning chamber 1 for surrounding the substrate (corresponds to the claimed "scattering prevention cup"). The Tomita washing device also includes a chamber rinsing nozzle 15 (corresponds to the claimed "second reverse side nozzle") and a back surface rinse nozzle 16 (corresponds to the claimed "first reverse side nozzle"). However, the chamber rinsing nozzle 15 and the back surface rinse nozzle 16 of the Tomita apparatus branch off from a single back surface rinse conduit 14 (see Fig. 1).

Thus, in Tomita, the cleaning liquid is not supplied via first and second cleaning liquid supply lines, but rather the cleaning liquid is supplied via a single cleaning liquid supply line 14 to both the chamber rinsing nozzle 15 and the back surface rinse nozzle 16. Accordingly, it is submitted that claim 8 is now clearly allowable over the teachings of Tomita.

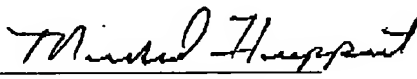
Doi is cited by the Examiner to teach a movable cup 80 including a lower cup 75 and an upper cup 76. However, Doi does not disclose the feature of claim 8 that is omitted in Tomita. Therefore, any combination of the Tomita and Doi references would not result in Applicant's invention as defined in claim 8.

In view of the above, it is submitted that the present application is now clearly in condition for allowance. The Examiner therefore is requested to enter the above amendment and pass this case to issue.

In the event that the Examiner has any comments or suggestions of a nature necessary to place this case in condition for allowance, then the Examiner is requested to contact Applicant's undersigned attorney by telephone to promptly resolve any remaining matters.

Respectfully submitted,

Shinji KAJITA et al.

By: 
Michael S. Huppert
Registration No. 40,268
Attorney for Applicants

MSH/kjf
Washington, D.C. 20006-1021
Telephone (202) 721-8200
Facsimile (202) 721-8250
January 13, 2009